AMENDMENTS TO THE CLAIMS:

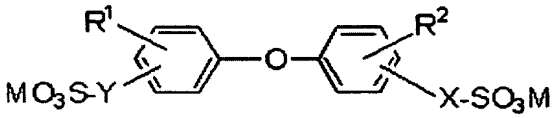
This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

1. (Currently Amended) A method for making a lithographic printing plate comprising the steps of:

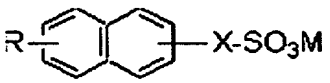
light-exposing to infrared radiation, a heat-sensitive presensitized plate of a positive-working mode for use in making a lithographic printing plate, said presensitized plate comprising a substrate and an image recording layer which is formed thereon and comprises a novolak resin containing xylenol as a monomer component and an infrared absorbing dye; and

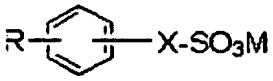
developing the light-exposed plate with an alkaline developing solution comprising at least one surfactant selected from the group consisting of anionic surfactants represented by the following formulas (I), (II), (III) and (IV) and amphoteric surfactants represented by the following formulas (V) and (VI):



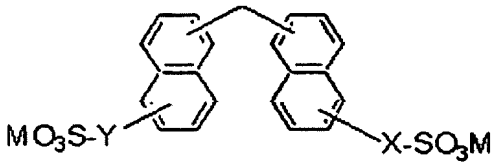
(I)

wherein R^1 and R^2 independently represent hydrogen atom or an alkyl group which may be in the form of linear or branched chain, X and Y independently represent a single bond or the formula -O-(CH_2CH_2O)n- wherein n is an integer of from 1 to 100, and M represents a monovalent alkali metal,

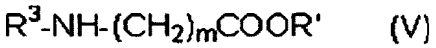

(II)

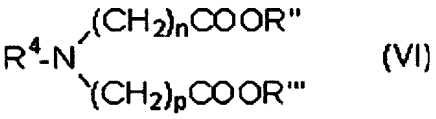

(III)

wherein, R represents hydrogen atom or an alkyl group which may be in the form of linear or branched chain, X represents a single bond or the formula $-O-(CH_2CH_2O)n-$ wherein n is an integer of from 1 to 100, and M represents a monovalent alkali metal,


(IV)

wherein X and Y independently represent a single bond or the formula $-O-(CH_2CH_2O)n-$ wherein n is an integer of from 1 to 100, and M represents a monovalent alkali metal


(V)


(VI)

wherein each R^3 and R^4 represents a hydrocarbon group having carbon atoms of from 2 to 30, and each R', R" and R"' represents a hydrogen atom or a monovalent alkali metal, and each m, n and p represents an integer of from 1 to 10.

2. (Original) The method of claim 1, wherein the xylenol used in the novolak resin is at least one selected from the group consisting of 3,5-xylenol, 2,3-xylenol, 2,5-xylenol and 3,4-xylenol.

3. (Original) The method of claim 1, wherein the novolak resin containing xylenol as a monomer component has a weight-average molecular weight of 500 to 10,000.

4. (Original) The method of claim 1, wherein the developing solution comprises at least one anionic surfactant.

5. (Canceled)

6. (Canceled)

7. (Original) The method of claim 1 wherein the developing solution comprises at least one amphoteric surfactant.

8.-11. (Canceled)

12. (Original) The method of claim 1 wherein the developing solution comprises at least one surfactant selected from the group consisting of anionic surfactants and amphoteric surfactants in an amount of from 0.001 to 10% by weight.